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Collana	Diffusion and defect forum, , 1012-0386 ; ; v. 277
Altri autori (Persone)	BekeD. L (Dezso L.)
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Nota di bibliografia	Includes bibliographical references and index.
Nota di contenuto	Diffusion and Diffusional Phase Transformations in Alloys; Committees, Organizers; Preface; Table of Contents; Section 1 - Diffusion and Reactions; Silicide Formation Reactions in a-Si/Co Multilayered Samples; Lateral Diffusion Spreading of Two Competitive Intermetallic Phases over Free Surface ; Theoretical Analysis and Atomistic Modelling of Diffusion and Stability of Pure Element Hollow Nanospheres and Nanotubes; Effect of Substrate Temperature on the Different Diffuseness of Subsequent Interfaces in Binary Multilayers Modeling of Diffusion Saturation of (+) Titanium Alloys by Nitrogen in the Rarefied Medium Suppression Criterion of the Phase Growth Based on Extremal Principles of Nonequilibrium Thermodynamics ; Model of Lateral Growth Stage during Reactive Phase Formation; Coupling of Electromigration and Non-Equilibrium Vacancies in Reactive Phase Growth; Section 2 - Driven Systems; Mechano-Chemistry; Interdiffusion in Solid Solutions; Models of Mutual Solubility Increasing under the Pulse Loading ; Cluster Dynamics Simulation of

Reactor Pressure Vessel Steels under Irradiation
The Ageing of Beryllium Bronze in the Pulse Magnetic Field
The Influence of Ti and Zr on the Diffusion of Isotope 63Ni in the Iron
Surface Layer at Electric-Spark Alloying in Carbon Containing
Environment; Effect of an Impulse Loading on Localization of Diffusing
Atoms in Metals; Section 3 - General Problems of Diffusion; Atomic
Mechanism of Carbon Diffusion in Cementite; Extended 'Five-Stream'
Model for Diffusion of Implanted Dopants in Silicon during Ultra-
Shallow Junction Formation in VLSI Circuits; Atomic-Migration-
Controlled Processes in Intermetallics
Dependence of Diffusion Paths on Thermodynamic Factors in Ternary
Systems
Simulation of Pressure Effects on Self-Diffusion in BCC Metals;
The Effect of Point Defects Interaction on Hydrogen Atom Diffusion in
FCC- and BCC-Metals ; Section 4 - Structural & Phase Transformations;
Numerical Simulation of Precipitates Evolution in Iron-Based Alloys; The
Analysis of the Selective Oxidation of Multicomponent Alloy; Complex
Phase Behavior of Systems with Negative Curvature Potentials
3D Monte Carlo Simulation of Phase Separation Kinetics in a Binary
Metallic Alloy with Vacancy Mediated Diffusion: Effect of Initial
Supersaturation Size-Induced Freezing Effect in Monte-Carlo
Simulations of Phase Separation Kinetics in Nanoparticles ; Diffusion
during Powder Metallurgy Synthesis of Titanium Alloys; Composition
Fluctuations in the Ostwald Ripening; Kinetic and Thermodynamic
Precipitation Parameters of the Pb-Sn Solid Solutions ; Section 5 -
Surface and Grain Boundary Diffusion
Surface Diffusion in Coadsorbed Layers with Different Mobilities of
Adsorbates: (Li +Dy) on Mo(112) and (Li+Sr) on W(112)

Sommario/riassunto

Diffusion-controlled processes still remain the most important and interesting phenomena in materials science. Among the problems which are currently to the fore, are the synergy of diffusion and morphological evolution, the initial stages of solid-state reactions, the analysis of nano- materials and related phenomena, thermo- and electromigration, and the reliability of solder joints and interconnects in microelectronic devices. A number of challenging problems still remain within the ""classical"" areas of nucleation, reactive- and inter-diffusion, phase growth in multicomponent and binary s
